

## Controlling nanostructures: A model with deposition, diffusion and aggregation

SIR - Röder et al. report nanometre-scale structures built by deposition of diffusing particles that aggregate on surfaces [1]. We report a computer model that mimics the same process, and produces morphologies that remarkably resemble the experimental structures. The model is defined as follows:

- (a) *Deposition*. Particles are deposited at randomly-chosen positions of the surface at a flux  $F$  per lattice site per unit time.
- (b) *Diffusion*. A cluster of connected particles is chosen at random and moved North, East, South or West by one lattice constant with a probability proportional to its mobility, which is given by  $D_s = D_1 s^{-\gamma}$ , where  $s$  is the number of particles in the cluster,  $D_1$  is the diffusion constant of the monomers and  $\gamma$  characterizes how the mobility of a cluster depends on its size.
- (c) *Aggregation*. If two particles come to occupy neighboring sites, they stick irreversibly.

The model can be tested by explicit comparison with the experimental data of [1], since there are no free parameters provided we introduce the experimental values for the flux and the diffusion constant. The diffusion constant of the monomers is given by  $D_1(T) = D_0 \exp(-E_d/kT)$  with  $E_d = 0.14eV$  [1], and  $D_0 = 5 \times 10^{11}$  [2]. Using the experimental values of the fluxes, we find  $F/D_1 = 10^3$  corresponds to Fig. 1a of [1], and  $F/D_1 = 10^{-10}$  to Fig. 1d. Figs.1a,b show results of the model with these flux values, and we note that the morphologies compare well with Figs. 1a and 1d of [1].

In general, the model allows one to distinguish the effects of deposition, diffusion and aggregation. We find that tuning the relative strength of, e.g., deposition and diffusion, generates a rich range of morphologies—including diffusion limited aggregation, cluster-cluster aggregation, and percolation [3]. The length and time scales characterizing these morphologies depend on experimentally-controllable parameters like deposition flux, and diffusion constant, raising the possibility that the model can be used for a controlled design

of nanostructure morphologies. Indeed, the model makes specific predictions, for example that the typical size of the DLA-like structures scales as  $(F/D_1)^{1/4}$ .

The model may be useful in many situations where diffusion occurs in the presence of continuous deposition. The model was originally motivated by thin film deposition experiments in which not *isolated atoms* but rather *aggregates* made up of compact spherical “molecules”,  $\approx 5$  nm diameter containing  $\approx 2000$  atoms are deposited on a surface [4]. The morphologies of Figs.1a,b also resemble experimental images obtained by such LECBD experiments on substrates maintained at low temperatures (compare Fig. 1b to Fig.3 of Ref.4).

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Fig.1: Morphologies obtained in the present model for two different values of flux  $F$ , diffusion constant  $D_1$ , and total surface coverage all chosen to correspond to the experimental parameters used in obtaining the data shown in Figs. 1a and 1d of Ref.1. (a)  $F/D_1 = 10^3$ , and total coverage of 0.012 (b)  $F/D_1 = 10^{-10}$ , and total coverage of 0.12. The simulation lattice had  $200 \times 200$  sites; the portion shown here corresponds to Figs. 1a and 1d of Ref.1, which are also a portion of the total experimental system. We set  $\gamma = 10$  (larger clusters rarely move—J.P. Bucher, private communication).